

Search Notes

Application No.

10/600,393

Examiner

Toniae M. Thomas

Applicant(s)

CHEN ET AL.

Art Unit

2822

Page 1

SEARCHED

| Class | Subclass | Date | Examiner |
|-------|----------|-----------|----------|
| 438 | 275 | 9/10/2004 | TMT |
| " | 770-777 | 9/10/2004 | " |
| " | 787-788 | 9/10/2004 | " |
| 438 | 791-792 | 9/10/2004 | TMT |
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INTERFERENCE SEARCHED

| Class | Subclass | Date | Examiner |
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**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

| | DATE | EXMR |
|--|-----------|------|
| USPAT US PG-Pub | 9/10/2004 | TMT |
| USPAT US PG-Pub | 9/9/2004 | TMT |
| USPAT US PG-Pub | 9/8/2004 | TMT |
| NPL database (silicon nitride and (atomic layer chemical vapor deposition or atomic layer deposition) | 9/10/2004 | TMT |
| NPL (silicon nitride and remote plasma enhanced chemical vapor deposition | 9/10/2004 | TMT |
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